



IEUVI Optics Contamination / Lifetime TWG Meeting

February 26, 2009 – San Jose, CA, USA

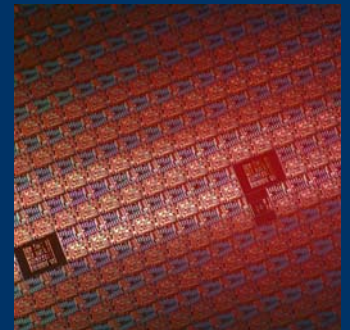
Chair: A. Wüest, SEMATECH

Co-chairs:

Asia/Pacific: A. Miyake, Canon

Europe: R. Verberk, TNO

US: T. Lucatorto, NIST



Organizational



- Sign-in list
- Not pre-registered:
Walk-in registration form
- Non-US citizens, not pre-registered:
Export Written Assurance Letter
- Evaluation form

Confidentiality Notice

- Non-Confidential Meetings-

- **This is a Non-Confidential Meeting**
- **This meeting may be open to non-members**
- **If proprietary or confidential information is disclosed,**
 - The discloser does so at his/her own risk
 - The discloser does so with the knowledge that the audience may include non-members
 - SEMATECH will not accept presentation materials marked “confidential” or “proprietary” for distribution

Export Compliance



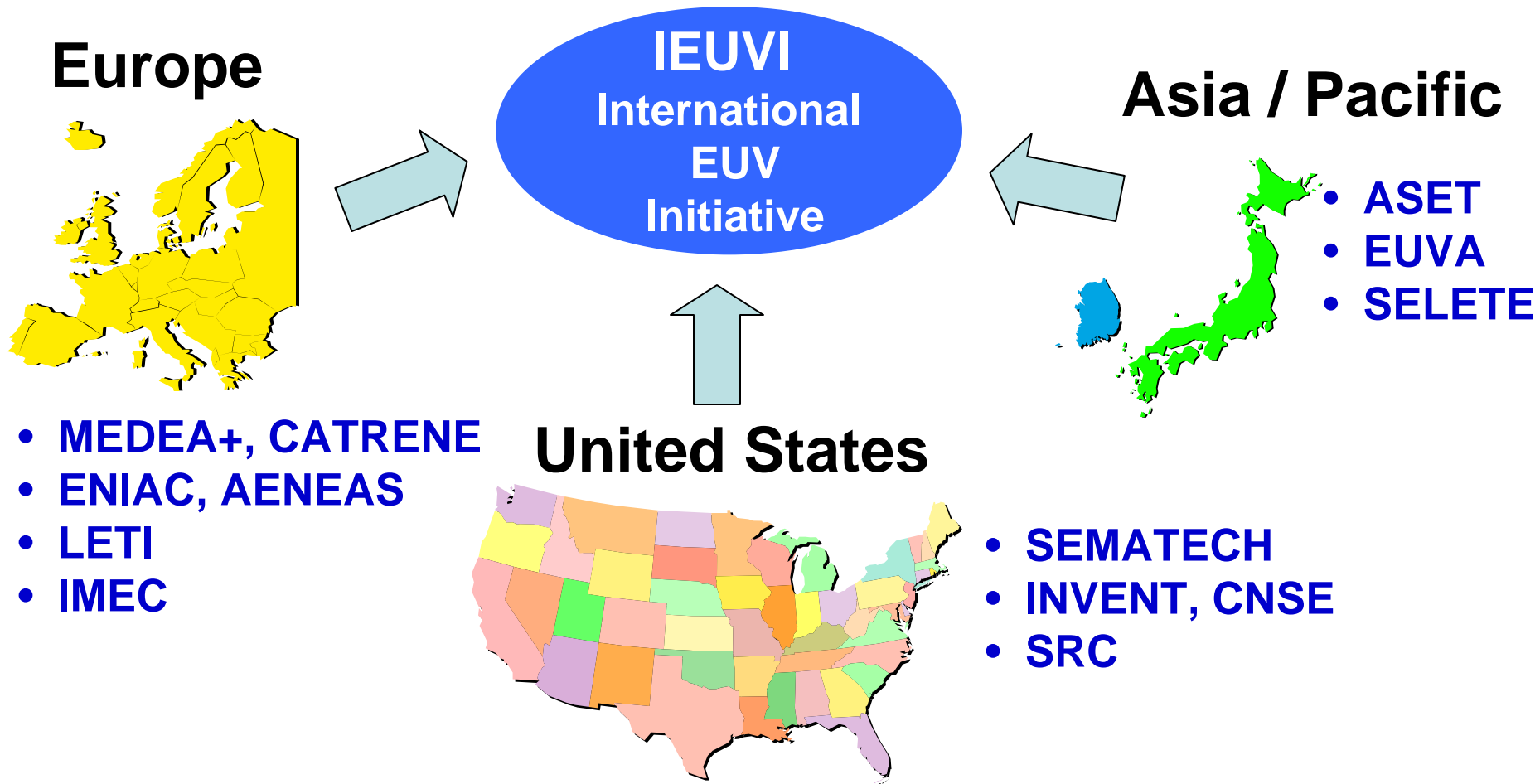
- U.S. export regulations require Foreign Nationals to sign a “**Written Assurance**” that technical information will not be disclosed to Restricted Countries*
 - Not required of member personnel with confirmed registration
- “Foreign National” means anyone not a U.S. citizen, Legal Permanent Resident, or INS “protected alien”
- Foreign Nationals of Restricted Countries* may not attend without the approval of the SEMATECH Export Manager
 - Applies to all, even member personnel
- * **Albania, Armenia, Azerbaijan, Belarus, Cambodia, China (PRC), Cuba, Georgia, Iran, Iraq, Kazakhstan, Kyrgyzstan, Laos, Libya, Macau, Moldova, Mongolia, North Korea, Russia, Sudan, Syria, Tajikistan, Turkmenistan, Ukraine, Uzbekistan, Vietnam.**

Questions?



- Please see your meeting chairperson IF
 - **You are a Foreign National who did not sign an Export Written Assurance**
 - **Unless pre-registered and a member employee**
 - **You are a Foreign National of a Restricted Country**
 - **You have questions about confidentiality or export requirements**

International EUV Initiative (IEUVI)



IEUVI Mission: To further the coordination of collaborative efforts among leading EUVL R&D consortia.

<http://www.ieuvi.org>

IEUVI Board

Chair:	Paolo Gargini	Intel		
Member Organizations:	CEA / LETI	(EU)	Selete	(JP)
	IMEC	(EU)	EUVA	(JP)
	MEDEA+, CATRENE, ENIAC, AENEAS	(EU)	SEMATECH	(US)

IEUVI Technical Working Groups (TWG)

Optics Contamination TWG

Chair:	Andrea Wüest	(US)	SEMATECH
Co-Chairs:	Tom Lucatorto	(US)	NIST
	Akira Miyake	(JP)	Canon
	Rogier Verberk	(EU)	TNO

Resist TWG

Chair:	Serge Tedesco	(EU)	CEA / LETI
Co-Chair	Jacque Georger	(US)	SEMATECH / Intel
	TBD	(AP)	

Mask TWG

Chair:	Kevin Orvek	(US)	SEMATECH / Intel
Co-Chairs:	Iwao Nishiyama	(JP)	Selete / NECEL
	Jinho Ahn	(KR)	Hanyang Univ.
	Jan Hendrik Peters	(EU)	AMTC

Source TWG

Chair:	Frank Goodwin	(US)	SEMATECH
Co-Chair:	Masashi Ogawa	(JP)	EUVA
	TBD	(EU)	

Introductions



Please introduce yourself

Agenda

San Jose, CA, USA - February 26, 2009



13:00	Welcome and Introductions	A. Wüest, SEMATECH
13:15	<ul style="list-style-type: none">• Effect of carbon contamination of EUV masks on imaging	Yu-Jen Fan, CNSE, U. Albany
13:35	<ul style="list-style-type: none">• Intel MET Status and Plans for 2009	Roman Caudillo, Intel
13:55	<ul style="list-style-type: none">• Update on Selete SFET	Iwao Nishiyama, Selete
14:15	Break	
14:35	<ul style="list-style-type: none">• Scaling study of carbon deposition on EUVL optics	A. Miyake, Canon
14:55	<ul style="list-style-type: none">• Ellipsometric and surface acoustic wave sensing of carbon contamination on EUV optics	F. Bijkerk, FOM Rijnhuizen
15:15	<ul style="list-style-type: none">• Discussion: Predicting optics carbonization from a knowledge of resist outgas composition	T. Lucatorto, NIST
15:30	<ul style="list-style-type: none">• Discussion	A. Wüest, SEMATECH
16:00	Adjourn	

Evaluation



- Please fill out the Evaluation Forms

Thank you



Thank you very much for your
participation and contribution!